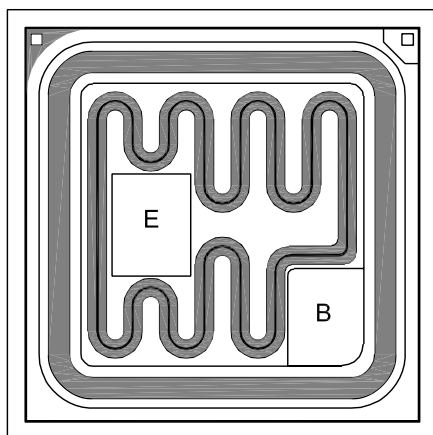


PROCESS DETAILS

Process	Epitaxial Planar
Die Size	19 x 19 MILS
Die Thickness	9.0 MILS
Base Bonding Pad Area	3.5 x 4.3 MILS
Emitter Bonding Pad Area	3.5 x 4.5 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 18,000Å

GEOMETRY



R1

BACKSIDE COLLECTOR

GROSS DIE PER 4 INCH WAFER

30,475

PRINCIPAL DEVICE TYPES

2N4403

2N5366

145 Adams Avenue
Hauppauge, NY 11788 USA
Tel: (631) 435-1110
Fax: (631) 435-1824
www.centalsemi.com

R0 (5- January 2006)